

**Notice of References Cited**

Application/Control No.

10/524,610

Applicant(s)/Patent Under  
Reexamination  
LAERMER ET AL.

Examiner

Hoang-Quan T. Ho

Art Unit

2818

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*		Document Number	Date	Name	Classification
		Country Code-Number-Kind Code	MM-YYYY		
	A	US-			
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	D	US-			
	E	US-			
	F	US-			
	G	US-			
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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